

Amendment to the Claims

This listing of Claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims

1. (Original) An exposure method for fabricating a liquid crystal display substrate, the method comprising the steps of:
 - aligning a reticle along a scanning direction, the reticle characterized by a reticle width and a reticle length and comprising a reticle pattern;
 - exposing the reticle pattern onto a portion of an exposure area on a substrate;
 - moving the substrate perpendicular to the scanning direction no greater than one-half of the reticle width; and
 - repeating the exposing and moving steps, thereby exposing an entirety of the exposure area at least twice.
2. (Original) The exposure method of claim 1, where the reticle length is at least as wide as the exposure area.
3. (Original) The exposure method of claim 1, where the exposing step is performed while the reticle and the substrate are moved simultaneously.
4. (Original) The exposure method of claim 3, where the reticle and the substrate are moved in the same direction.
5. (Original) The exposure method of claim 1, where the exposing step comprises the step of scanning the reticle along a longer axis direction of the reticle.

6. (Canceled)

7. (Original) The exposure method of claim 1, where the exposing step comprises illuminating along a length direction perpendicular to the scanning direction.

8. (Original) The exposure method of claim 1, where the reticle pattern is repetitive.

9. (Original) The exposure method of claim 1, where the exposing step comprises the step of equimultiple erect imaging to transcribe the reticle pattern onto the exposure region in 1:1 proportion.

10. (Original) The exposure method of claim 1, wherein the moving step comprises the step of moving the substrate approximately one-half of the reticle width.

11. (Withdrawn) An exposure apparatus for exposing a reticle onto an exposure area of a substrate, the apparatus comprising:

a mask stage for supporting a reticle comprising a reticle pattern, the reticle pattern characterized by a reticle width, a reticle length, and a scanning direction;

a substrate stage for supporting an LCD substrate comprising an exposure area, the substrate stage moving the LCD substrate perpendicular to the scanning direction no greater than one-half of the reticle width between exposures of the reticle; and

an illuminative optical system for exposing the reticle pattern along the scanning direction onto a portion of the exposure area,

the substrate stage and illuminative optical system repeatedly moving and exposing to expose an entirety of the exposure area at least twice.

12. (Withdrawn) The exposure apparatus of claim 11, where the reticle length is longer than the reticle width and where the scanning direction is along the reticle length.

13. (Withdrawn) The exposure apparatus of claim 11, where the reticle pattern is repetitive.

14. (Withdrawn) The exposure apparatus of claim 11, where the substrate stage moves the substrate perpendicular to the scanning direction approximately one-half of the reticle width so that the entirety of the exposure area is exposed twice.

15. (Withdrawn) The exposure apparatus of claim 11, where the substrate stage moves the substrate perpendicular to the scanning direction less than one-half of the reticle width so that the entirety of the exposure area is exposed more than twice.

16. (Withdrawn) The exposure apparatus of claim 11, where the illuminative optical system is an equimultiple erect optical system.

17. (Withdrawn) The exposure apparatus of claim 11, where the reticle length is at least as wide as the exposure area.

18. (Withdrawn) The exposure apparatus of claim 11, where the reticle and the LCD substrate move together.

19. (Withdrawn) An exposure apparatus for exposing a reticle onto an exposure area of a substrate, the apparatus comprising:

a substrate stage for moving a substrate along an X-axis and a Y-axis that is perpendicular to the X-axis;

a mask stage for moving a reticle along the Y-axis; and

an illuminative optical system for taking a plurality of exposures of the reticle along the Y-axis onto an exposure region on the substrate,

the mask stage moving the substrate along the X-axis in order to expose an entirety of the exposure region at least twice.

20. (Withdrawn) The exposure apparatus of claim 19, where the reticle is characterized by a reticle width and a reticle length, the reticle length disposed along the Y-axis and greater than the reticle width.

21. (Withdrawn) The exposure apparatus of claim 19, where the reticle comprises a repetitive reticle pattern.

22. (Withdrawn) The exposure apparatus of claim 19, where the mask stage moves the substrate along the X-axis in order to expose an entirety of the substrate twice.

23. (Withdrawn) The exposure apparatus of claim 22, where the reticle is characterized by a reticle width, and where the mask stage moves the substrate along the X-axis by approximately one-half of the reticle width.

24. (Withdrawn) The exposure apparatus of claim 19, where the mask stage moves the substrate along the X-axis in order to expose an entirety of the substrate more than twice.

25. (Withdrawn) The exposure apparatus of claim 24, where the reticle is characterized by a reticle width, and where the mask stage moves the substrate along the X-axis by less than one-half of the reticle width.

26. (Withdrawn) The exposure apparatus of claim 19, where the illuminative optical system scans the reticle along the Y-axis.

27. (Withdrawn) The exposure apparatus of claim 19, where the substrate and reticle move together along the Y-axis.

28. (Withdrawn) The exposure apparatus of claim 27, where the substrate and reticle move together along the Y-axis during exposure at the same speed.

29. (Withdrawn) The exposure apparatus of claim 19, where the illuminative optical system generates an illumination region of the reticle comprising a length direction perpendicular to the Y-axis.

30. (Withdrawn) The exposure apparatus of claim 19, where the reticle is at least as long as the exposure region along the Y-axis.